

# Supporting Information

## Growth modulation of nonlayered 2D-MnTe and MnTe/WS<sub>2</sub> heterojunction for high-performance photodetector

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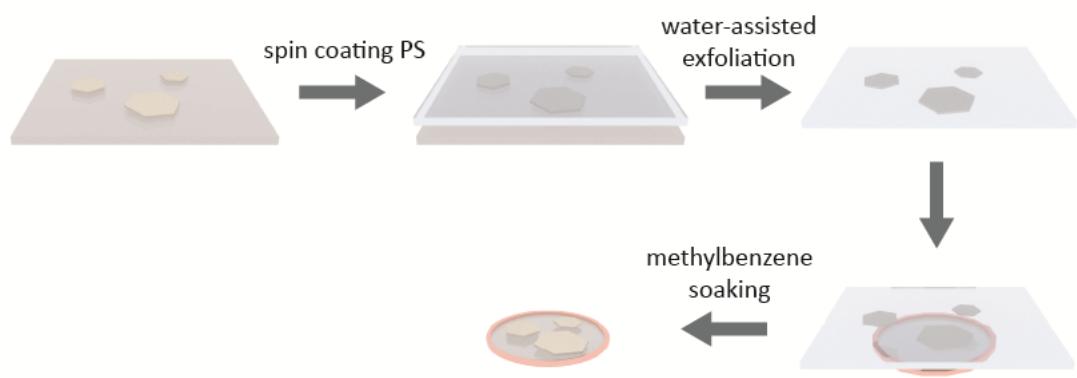


Figure S1. Schematic diagram of the process to transfer MnTe nanosheets onto a copper mesh.

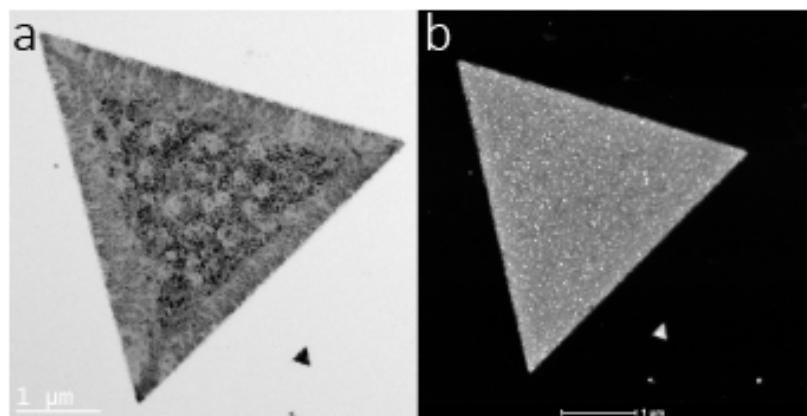


Figure S2. Low-magnification transmission electron microscopy images (a) and high-angle annular dark-field (HAADF) image (b) of MnTe nanosheet.

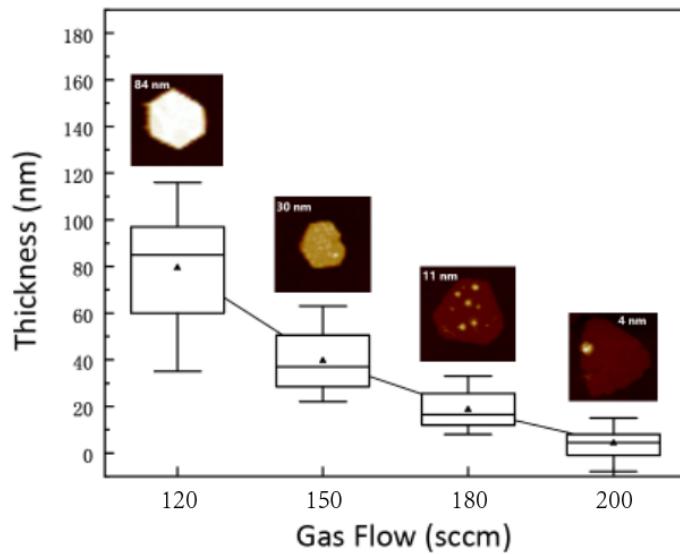


Figure S3. The average thickness of MnTe nanosheets grown at different gas flows.

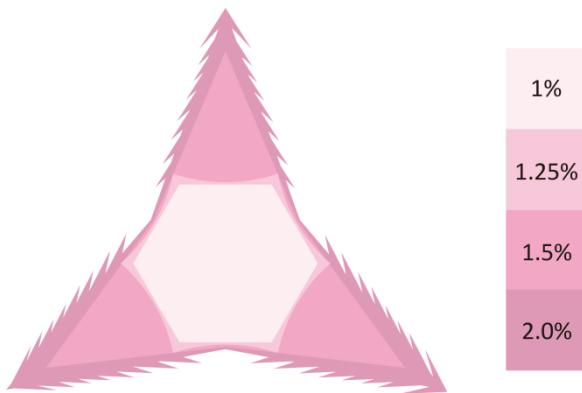


Figure S4. Morphological evolution of MnTe nanosheets as single-domain net growth rate increases.

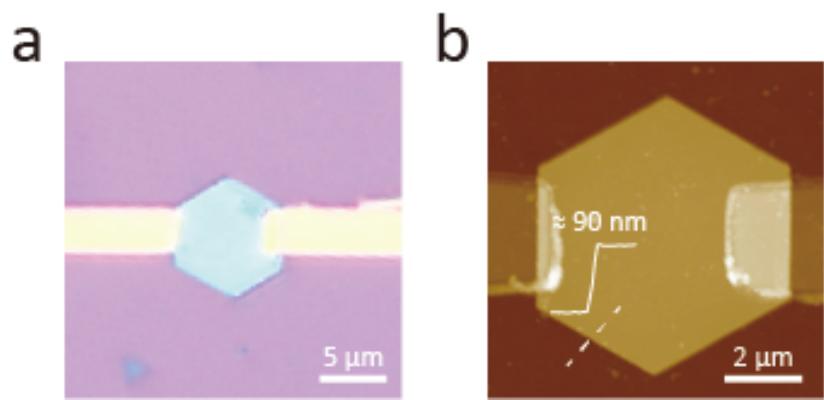


Figure S5. The optical microscopy image (a) and the AFM image (b) of MnTe-based FET device.

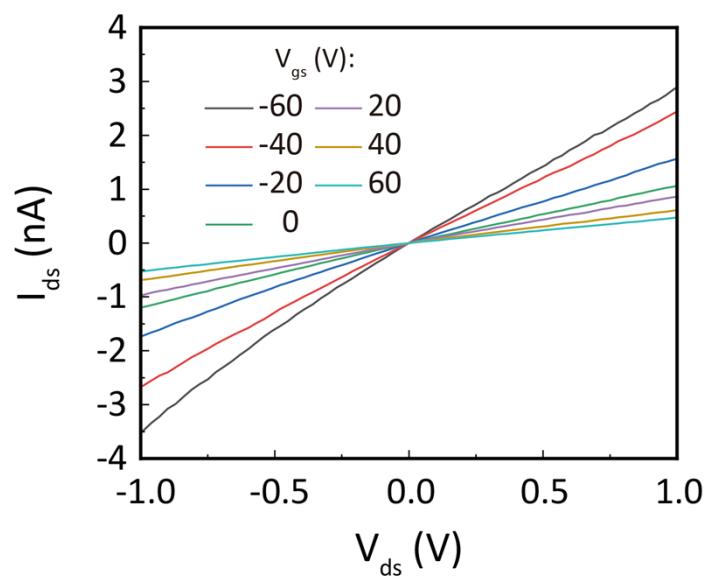


Figure S6.  $I_{ds}$ - $V_{ds}$  output characteristics of MnTe-based FET.

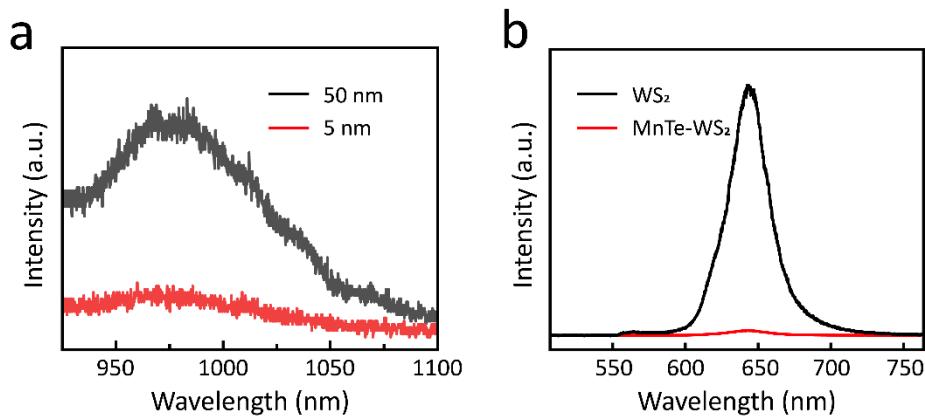


Figure S7. (a)PL spectra of MnTe nanosheets with different thicknesses. (b) PL spectra of a few layers of WS<sub>2</sub> nanosheets and MnTe/WS<sub>2</sub> heterostructure.

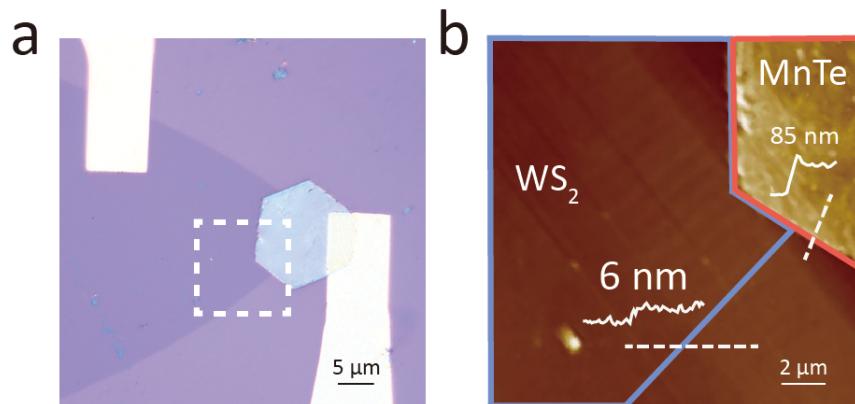


Figure S8. The optical microscopy image (a) and the AFM image (b) of MnTe-WS<sub>2</sub> heterojunction photodetector device.

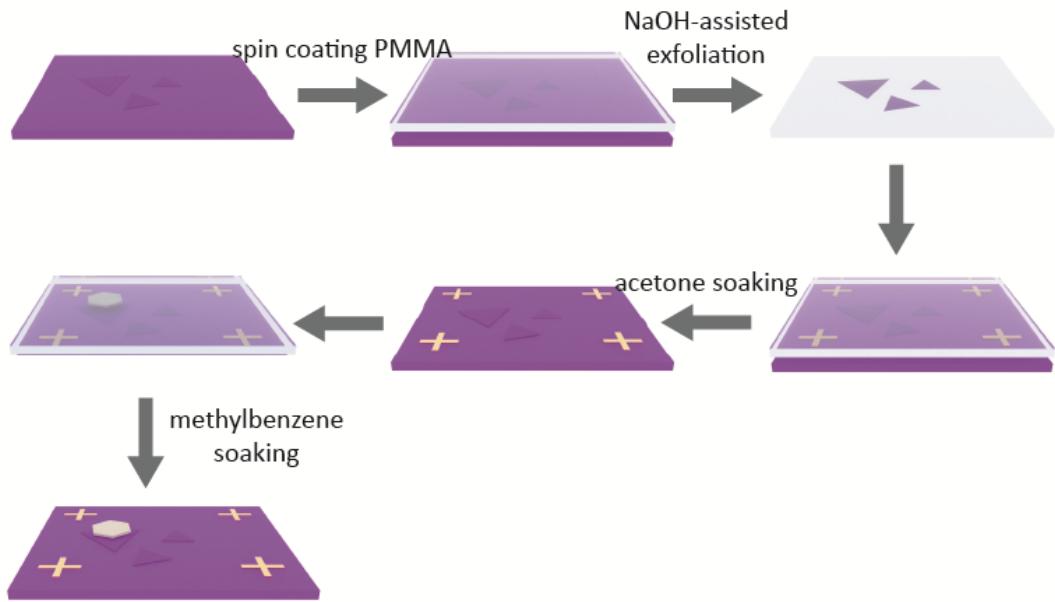


Figure S9. Schematic diagram of the process to fabricate the MnTe/WS<sub>2</sub> photodetector.

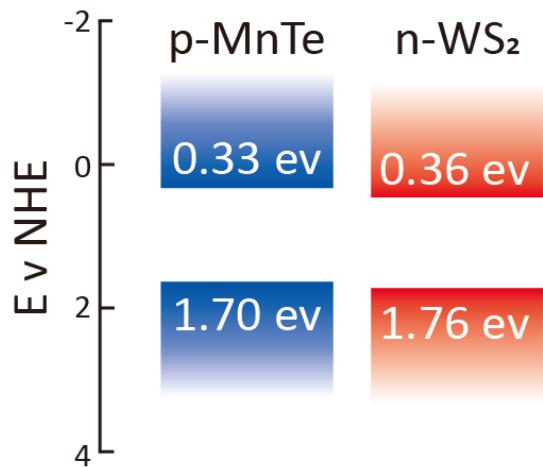


Figure S10. Band alignment of MnTe/WS<sub>2</sub> heterojunction.

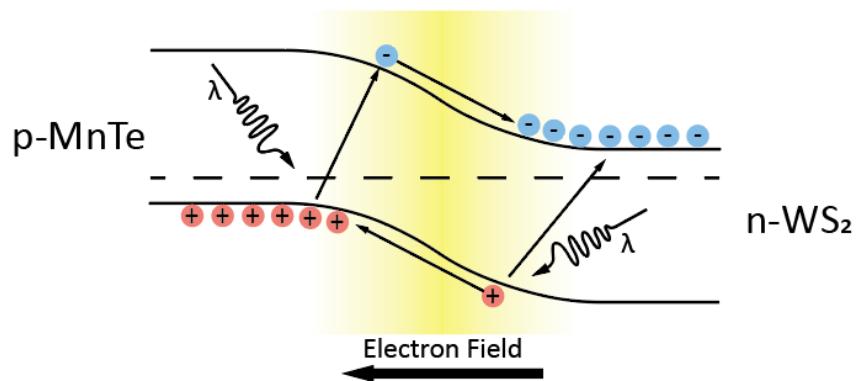


Figure S11. The mechanism diagram of MnTe-WS<sub>2</sub> heterojunction photodetector.

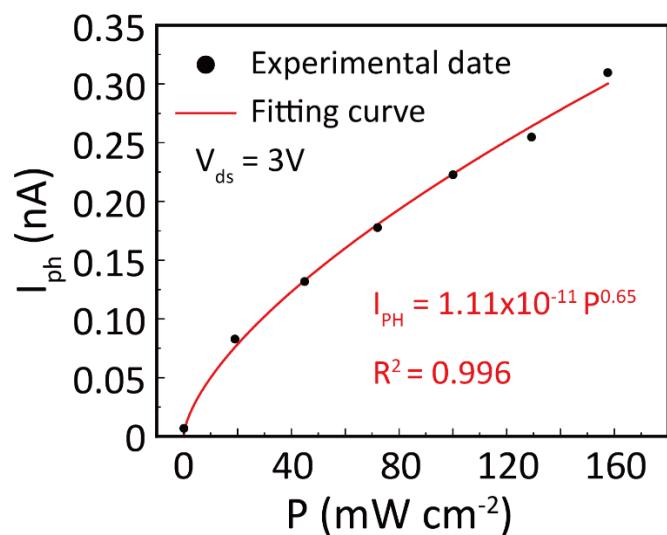


Figure S12. The fitted curve of power density vs. photocurrent.

Table S1. Comparison of the photodetector performance with other 2D heterostructures.

Materials	Method	Wavelength (nm)	Photoresponsivity (A W <sup>-1</sup> )	Detectivity (Jones)	Reference
MnTe/WS <sub>2</sub>	CVD-restacking	637	0.271	1.23×10 <sup>10</sup>	This work
WS <sub>2</sub> /MoS <sub>2</sub>	CVD	532	0.00436	4.36×10 <sup>13</sup>	1
WSe <sub>2</sub> /SnS <sub>2</sub>	CVD	520	0.108	4.71×10 <sup>10</sup>	2
GaSe/MoS <sub>2</sub>	CVD	300	0.065	-	3
GaSe/MoSe <sub>2</sub>	CVD	white light	0.03	-	4
SnS <sub>2</sub> /MoS <sub>2</sub>	CVD	638	1.36	-	5
GaSe/Gasb	MBE	637	0.1	2.2×10 <sup>12</sup>	6
ReS <sub>2</sub> /ReSe <sub>2</sub>	Exfoliated-restacking	550	0.021	-	7
MoTe <sub>2</sub> /MoS <sub>2</sub>	Exfoliated-restacking	473	0.06	1.60×10 <sup>10</sup>	8
BP/InSe	Exfoliated-restacking	455	0.017	-	9

## References

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